

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>	Docket Number (Optional) TWI-32410	Application Number NEW
	Applicant(s) Abdurrahman Sezginer et al.	
	Filing Date HEREWITH	Group Art Unit Unknown

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
PO	AA	US 2002/0135875	09/26/2002	Niu et al.	359	564	02/27/2001
PO	AB	US 2002/0158193	10/31/2002	Sezginer et al.	250	237	02/12/2002
PO	AC	US 2003/0042579	03/06/2003	Schulz	257	629	04/29/2002
PO	AD	US 2003/0043372	03/06/2003	Schulz	356	327	04/29/2002
PO	AE	US 2003/004702	03/06/2003	Schulz	430	30	04/29/2002
PO	AF	6,532,076	03/11/2003	Sidorowich	356	630	04/04/2000

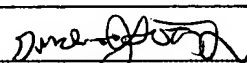
FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
PO	AG	WO 02/25723 A2	03/28/2002	PCT	H01L	21/66		

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

PO	AH	W. Yang et al., "A Novel Diffraction Based Spectroscopic Method For Overlay Metrology," <i>SPIE's 28th Annual International Symposium and Education Program and Microlithography</i> , February 2003, pp. 9.					
PO	AI	T.A. Germer, "Measurement of lithographic overlay by light scattering ellipsometry," <i>Proceedings of SPIE, Surface Scattering and Diffraction and Advanced Metrology II</i> , Vol. 4780, 2002, pp. 72-79.					
PO	AJ	H.T. Huang et al., "Scatterometry-Based Overlay Metrology," <i>SPIE (Microlithography 2003)</i> , Vol. 5038, 2003. 12 pages in length.					
PO	AK	M. Adel et al., "Characterization of Overlay Mark Fidelity," <i>SPIE Meeting on MicroLithography</i> , February 2003, 8 pages in length.					

Examiner 	Date Considered 3/25/05
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	